

Amendments to the Claims

This listing of claims will replace all prior versions and listings of claims in the application.

Listing of Claims

1. (Currently Amended) A system for retaining a silicon wafer during semiconductor processing and subsequently releasing it, the system comprising:

a chuck equipped with a lifting mechanism that comprises at least one extendable lifting pin driven by a solenoid, and wherein current from the solenoid is a measured current, wherein the chuck is dimensioned to receive the wafer and the lifting mechanism is adapted to release the wafer from the chuck;

a voltage source operably coupled to the chuck, and adapted to impart an electric charge to the chuck and an opposite electric charge to the wafer, producing an electrostatic attraction between the wafer and the chuck;

a sensor adapted to measure a force due to the electrostatic attraction, wherein said force is in opposition to an applied force provided by the lifting mechanism, and wherein the sensor comprises a current monitor adapted for measuring a—the current from the solenoid, wherein the measured current is proportional to the applied lifting force; and

a control system adapted to receive the measured current and neutralize the electrostatic attraction between the wafer and the chuck by reversing a polarity of the voltage source, thereby reducing the electric charge to the chuck and the opposite electric charge to the wafer until the force due to the electrostatic attraction reaches a predetermined minimum, as indicated by the sensor.

2. (Cancelled)

3. (Previously Presented) The system as recited in claim 1, wherein the sensor comprises a load cell adapted to measure the force opposing the lifting mechanism and to forward the measured force to the control system.

4. (Cancelled)

5. (Previously Presented) The system as recited in claim 1, wherein the control system is further adapted to limit the current to the solenoid until the force opposing the lifting mechanism reaches a predefined minimum, and then to increase the current to the solenoid to enable the lifting mechanism to raise the wafer off the chuck.

6. (Cancelled)

7. (Previously Presented) The system as recited in claim 1, wherein the sensor comprises a pressure sensor adapted to measure a pressure equivalent to force opposing the lifting mechanism and to forward the measured pressure to the control system.

8. (Original) The system as recited in claim 7, wherein the control system is further adapted to limit the pressure to the piston until the pressure opposing the extensible lifting pin reaches a minimum, and then to increase the pressure to the piston to enable the lifting mechanism to raise the wafer off the chuck.

9. (Previously Presented) The system as recited in claim 1, wherein the sensor comprises an orifice at an interface between the wafer and the chuck, operably coupled to the chuck are:

a line through which pressure may be applied to the wafer through the orifice; and

a sensor adapted to indicate to the control system the presence or absence of pressure at the orifice.

10. (Original) The system as recited in claim 9, wherein the control system is further adapted to limit the pressure to the piston until the pressure at the orifice is absent, and then to increase the pressure to the piston to enable the lifting mechanism to raise the wafer off the chuck.

11. (Previously Presented) A method for releasing a semiconductor wafer, comprising:

sensing electrostatic attraction between a wafer and a chuck electrically charged opposite one another;

measuring a current proportional to an applied lifting force;

neutralizing the electrostatic attraction by reversing the electrical charge applied to the wafer and the chuck; and

when the sensed electrostatic attraction achieves a pre-determined minimum, lifting the wafer from the chuck by driving a solenoid coupled to an extendable pin and extending the pin against a backside of the wafer, and wherein said measuring comprises determining the current in the solenoid needed to oppose a downward force of the wafer against the extendable pin prior to lifting the wafer.

12. (Original) The method as recited in claim 11, further comprising:

placing the wafer on the chuck; and

charging the wafer and chuck opposite one another.

13. (Cancelled)

14. (Previously Presented) The method as recited in claim 11, wherein said sensing comprises reading a pressure of the pin against the backside of the wafer prior to lifting the wafer.

15. - 16. (Cancelled)

17. (Previously Presented) The method as recited in claim 11, further comprising limiting the current until the force of the wafer reaches a minimum, and then increasing the current to enable lifting the wafer.

18. (Original) The method as recited in claim 11, wherein said lifting comprises pneumatically driving a pressure-actuated piston bearing against a backside of the wafer.

19. (Original) The method as recited in claim 18, wherein said sensing comprises sensing the pressure within the pressure-actuated piston during times when the piston bears against the backside of the wafer.

20. (Original) The method as recited in claim 19, further comprising limiting the pressure within the pressure-actuated pistons until the pressure brought to bear against the pistons reaches a pre-determined minimum, and then increasing the to the pistons to enable lifting the wafer.

21. (Original) The method as recited in claim 18, further comprising reading a pressure at an orifice configured at the interface between the wafer and the chuck.

22. (Original) The method as recited in claim 18, further comprising limiting the pressure to the piston until the pressure at the orifice is absent, and then increasing the pressure to enabling lifting the wafer.